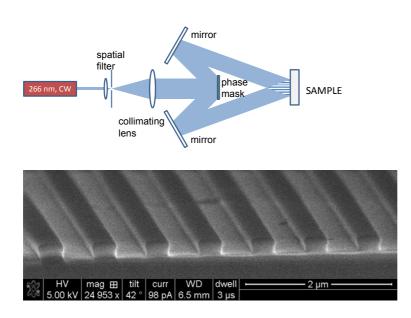
DEEP UV-LASER LITHOGRAPHY

At the laserphysics group, we use an in-house built interferometric UV-laser lithographic system to pattern photoresist gratings with periodicities ranging from 400-900 nm, as depicted below. This lithographic set-up is of utmost importance for the fabrication of the next generation of non-linear optical devices, where we need nanometer precision on the designed periodicity of the grating. This bachelor-thesis project consists in developing a calibration set-up to accurately measure the grating periodicity. It involves both system design and experimental implementation.



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